## Supplementary Information (SI)

#### For

# Simple and rapid gas sensing using a single-walled carbon nanotube field effect transistor-based logic inverter

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## 1. SWCNT-FETs



**Fig. S1**. **a** Schematic view of the transistor geometry **b** Typical scanning electron imaging showing SWCNTs connecting the source and drain electrodes

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**Fig. S2**. **a** (left)  $I_{ds}$ - $V_g$  characteristic of the p-type SWCNT-FET ( $V_{DS}$  = 1 V) (right) schematic view of the p-type SWCNT-FET **b** (left)  $I_{ds}$ - $V_g$  characteristic of the n-type SWCNT-FET ( $V_{DS}$  = -1 V) (right) schematic view of the n-type SWCNT-FET

## 2. Gas enclosure characteristic



Fig. S3. (left) Schematic view of the gas delivery system (right) picture of the gas enclosure

## 3. Desorption



Fig. S4.  $I_{ds}$ -V<sub>g</sub> curves under N<sub>2</sub> after an exposure to NO<sub>2</sub>

#### 4. Device response calculation

The response of the device is taken as shown in the figure. For each defined time (here an example is shown for the response after 15 minutes of gas exposure), the response was considered as the average of half of the  $V_{out}$  value on three different pulses (green line sections in Figure S5). The error on  $V_{out}$  under  $N_2$  and  $NO_2$  exposures is defined as the standard deviation of the average.



**Fig. S5.** Output voltage of the inverter after exposure to 10 ppm of NO<sub>2</sub> gas for 15 minutes. The response at 15 minutes is measured using the green sections of the curve.

#### 5. Stability and reproducibility of the response

The reproducibility and stability of the response of our p-device (active part of the sensor) under NO<sub>2</sub> exposure has been tested and reported in a previous work<sup>8</sup>, nevertheless the reproducibility of the response of the inverter was also tested. The response of the device was measured for three different NO<sub>2</sub> concentrations (Test 1), and re-measured after several weeks (Test 2).



Fig. S6. Response of the same device as a function of NO<sub>2</sub> concentration measured several weeks apart.

### 6. Output voltage as a function of time under NO<sub>2</sub> exposure



• V<sub>DD</sub> = 2 V

**Fig. S7** Output voltage of the inverter as a function of time under NO<sub>2</sub> exposure for a square input voltage of alternatively -4 V and -11 V,  $V_{DD} = 2 V$ .





**Fig. S8** Output voltage of the inverter as a function of time under  $NO_2$  exposure for a square input voltage of alternatively -4 V and -11 V,  $V_{DD} = 4 V$ .

• V<sub>DD</sub>= 6 V



**Fig. S9** Output voltage of the inverter as a function of time under  $NO_2$  exposure for a square input voltage of alternatively -4 V and -11 V,  $V_{DD} = 6 V$ .

#### 7. Limit of Detection (LOD) calculation

For all three  $V_{DD}$  used, a calibration curve for low concentrations has been determined by performing a linear fit of the first three points of the curve R=f(C) where R is the response of the device and C the concentration in ppm. The obtained values of r<sup>2</sup> available in Table 1 confirm the linear response of the device in this concentration range.



Fig. S10 Response of the device under NO<sub>2</sub> exposure and linear fits at low concentrations (green curve)

V <sub>DD</sub> (V)	ai	bi	r <sup>2</sup>
2 (i=1)	1.79127 ± 0.12866	0.08378 ± 0.20042	0.99487
4 (i=2)	2.37032 ± 0.30571	0.08026 ± 0.22286	0.98364
6 (i=3)	2.73325 ± 0.62948	-0.26988± 0.48329	0.94963

Table S1 Parameters of the linear fits.

Then for each  $V_{DD}$  used, the response of the device for a concentration C = 0 ppm of NO<sub>2</sub> was measured. The obtained values are detailed in Table 2. According to IUPAC definition the LOD is defined by the lowest discernible signal over the background signal. Here we consider that the lowest response that we can detect as 3 three times the average of the error on the signal of the blank, obtained with at least four measurements of the blank signal. The calculated LOD is given by equation (1):

V <sub>DD</sub> = 2 V		V <sub>DD</sub> = 4 V		V <sub>DD</sub> = 6 V	
Response C=0	Error	Response C=0	Error	Response C=0	Error
0	0.64632	0	0.43287	0	0.55712
0	0.45518	0	0.45107	0	0.5322
0	0.55686	0	0.5002	0	0.44708
0	0.54666	0	0.36927	0	0.40975
-	-	0	0.5024	0	0.59831
Mean : 0.55+/- 0.08		Mean : 0.45+/-0.05		Mean : 0.51+/-0.08	

Table S2. Response of the device under N<sub>2</sub> (*i.e.* NO<sub>2</sub> concentration at 0 ppm)

The LOD is then obtained using the linear calibration curve, the error is determined using the error on the slope and the standard deviation of the average value of the blank.

V <sub>DD</sub> (V)	Blank	Blank	Slope	Slope	LOD (ppm)	LOD
	measurement	measurement		error		error
		error				(ppm)
2	0.55125	0.07814	1.79127	0.12866	0.92	0.20
4	0.45116	0.05494	2.37032	0.30571	0.57	0.14
6	0.50889	0.07829	2.73325	0.62948	0.56	0.21

**Table S3.** Calculation of the LOD

8.	Comparison	of SWCNT-FET	based devic	es for NO <sub>2</sub>	sensing properties
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Device Architecture	Limit of	Minimum measured	Sensitivity	Reference
	Detection (LOD) [ppm]	Concentration [ppm]	[1/ppm]	
FET sensors based on	-	200	-	1
individual SWCNTs		0.3		2
FET sensors based on	-	1	-	3
individual, suspended				
SWCNTs				
FET sensors based on	-	20	-	4
SWCNT networks	0.044	6	0.034 ± 0.002	5
	0.069	0.5	0.238	6
FET sensors based on low	-	0.86	-	7
density SWCNT networks				
FET sensors based on few	0.086	0.1	-	8
individually connected				
SWCNTs				
Inverter sensors based on	0.57 +/- 0.14	0.6	-	This work
p-SWCNT-FET and n-				
SWCNT-FET containing few				
individually connected				
SWCNTs				

**Table S4.** Comparison of SWCNT-FET based gas sensor performances.

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